

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|---------|--|-------------------------|------------------|---------|------------------|
| L1 | 1103140 | (wafer substrate) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:45 |
| L2 | 389628 | 1 and (first near5 (layer material film)) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:45 |
| L3 | 307273 | 2 and (second near5 (layer material film)) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:07 |
| L4 | 67766 | 3 and (CMP polish\$3) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:46 |
| L5 | 25982 | 4 and ((first second) near5 region) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:46 |
| L6 | 25417 | 5 and surface | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:10 |
| L7 | 11293 | 6 and ((first second) near5 thickness) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:11 |
| L8 | 5748 | 7 and polysilicon | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:11 |
| L9 | 5251 | 8 and pattern\$4 | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:13 |
| L10 | 4820 | 9 and (resist mask) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:14 |
| L11 | 3150 | 10 and ((first near8 region) near10 (second near8 region)) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:22 |
| L12 | 3664 | 10 and ((low\$3 bottom) near8 (region part surface)) | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:23 |
| L13 | 2461 | 11 and 12 | US-PGPU B; USPAT; USOCR | OR | ON | 2007/09/08 08:23 |

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|-----|---------|--|--|----|----|---------------------|
| L14 | 1612617 | (wafer substrate) | FPRS; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/09/08 08:45 |
| L15 | 122488 | 14 and (first near5 (layer material film)) | FPRS; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/09/08 08:46 |
| L16 | 3494 | 15 and (CMP polish\$3) | FPRS; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/09/08 08:46 |
| L17 | 447 | 16 and ((first second) near5 region) | FPRS; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/09/08 08:46 |

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|-------|--------|--|-----------|------------------|---------|------------------|
| L1 | 193285 | (wafer substrate).clm. | US-PGPU B | OR | ON | 2007/09/08 09:21 |
| L2 | 130434 | (first near5 (layer material film)).clm. | US-PGPU B | OR | ON | 2007/09/08 09:21 |
| L3 | 123333 | (second near5 (layer material film)).clm. | US-PGPU B | OR | ON | 2007/09/08 09:22 |
| L5 | 15366 | (CMP polish\$3).clm. | US-PGPU B | OR | ON | 2007/09/08 09:23 |
| L6 | 154799 | (polysilicon conduct\$3).clm. | US-PGPU B | OR | ON | 2007/09/08 09:24 |
| L7 | 2295 | 1 and 2 and 3 and 5 and 6 | US-PGPU B | OR | ON | 2007/09/08 09:24 |
| L9 | 172381 | ((first second) near5 (surface region)).clm. | US-PGPU B | OR | ON | 2007/09/08 09:25 |
| L10 | 1584 | 7 and 9 | US-PGPU B | OR | ON | 2007/09/08 09:26 |
| L11 | 97019 | ((low\$3 bottom) near8 (region part surface)).clm. | US-PGPU B | OR | ON | 2007/09/08 09:32 |
| L12 | 558 | 10 and 11 | US-PGPU B | OR | ON | 2007/09/08 09:32 |
| L13 | 106742 | (pattern\$4).clm. | US-PGPU B | OR | ON | 2007/09/08 09:41 |
| L14 | 318 | 13 and 12 | US-PGPU B | OR | ON | 2007/09/08 09:41 |